

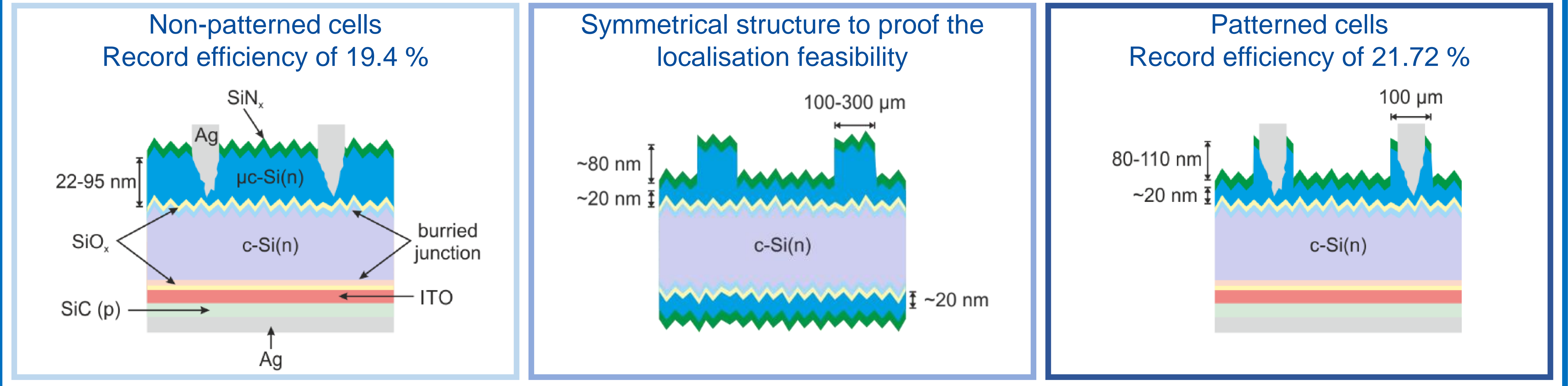
# Localisation of front side passivating contacts for direct metallisation of high-efficiency c-Si solar cells

Frank Meyer<sup>1</sup>, Andrea Ingenito<sup>1,2</sup>, Juan J. Diaz Leon<sup>2</sup>, Xavier Niquille<sup>1</sup>, Christophe Allebé<sup>2</sup>, Sylvain Nicolay<sup>2</sup>, Franz-Josef. Haug<sup>1</sup> and Christophe Ballif<sup>1,2</sup>

<sup>1</sup> *École Polytechnique Fédérale de Lausanne (EPFL), Institute of Microengineering (IMT), Photovoltaics and Thin-Film Electronics Laboratory (PVLAB), Rue de la Maladière 71b, 2000 Neuchâtel, Switzerland*  
<sup>2</sup> *Swiss Center for Electronics and Microtechnology (CSEM), Rue Jaquet-Droz 1, 2000 Neuchâtel, Switzerland*

## Firing Through Process: PVLAB strategies

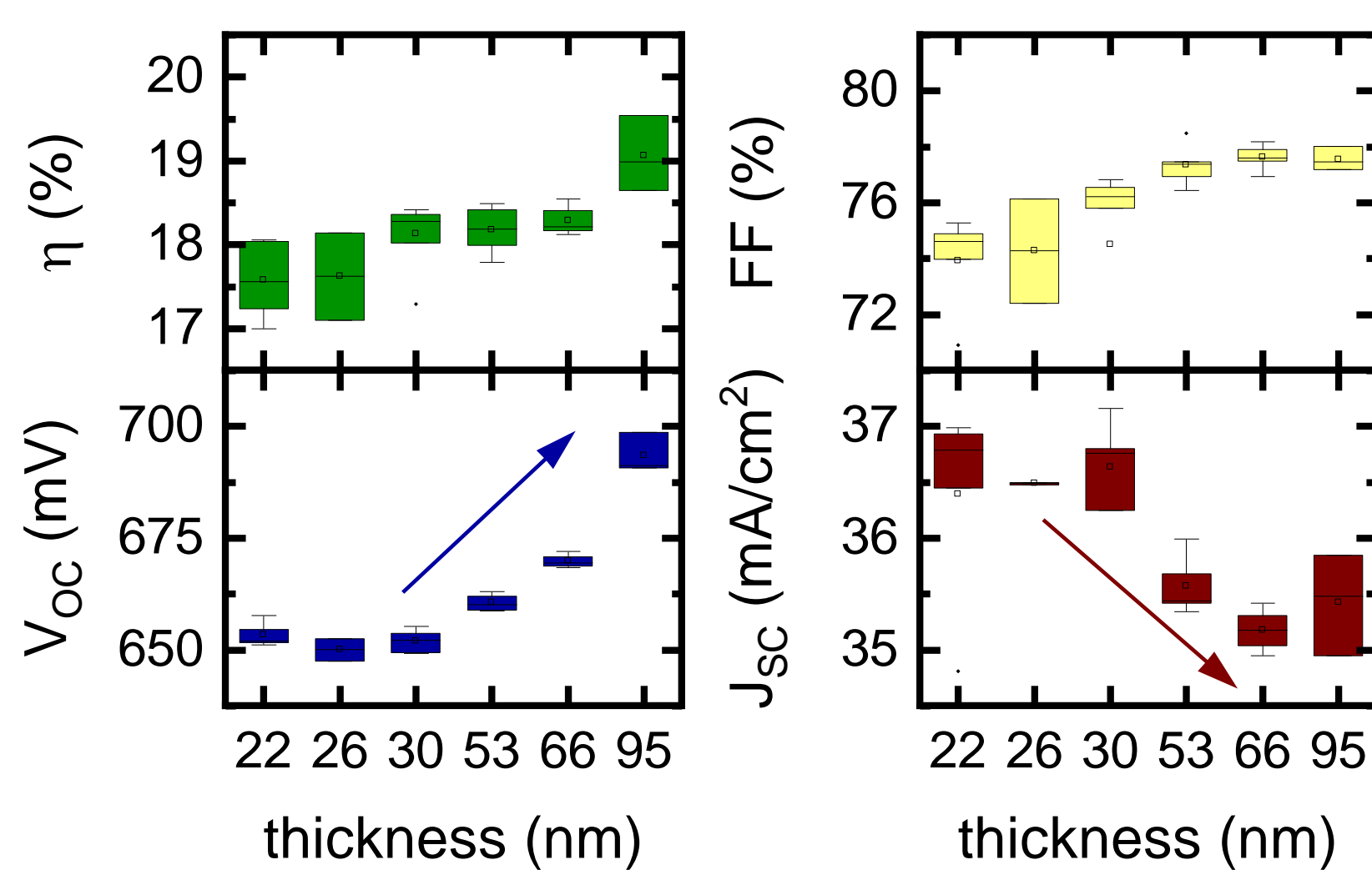
Passivating contacts are keys to enable conversion efficiency  $\geq 26\%$ <sup>[1,2,3]</sup> and are compatible with firing through process. To ensure high  $V_{OC}$ , thick passivating contacts must be integrated at the front without compromising photo-generation of carriers.



### Non-Patterned Solar Cells

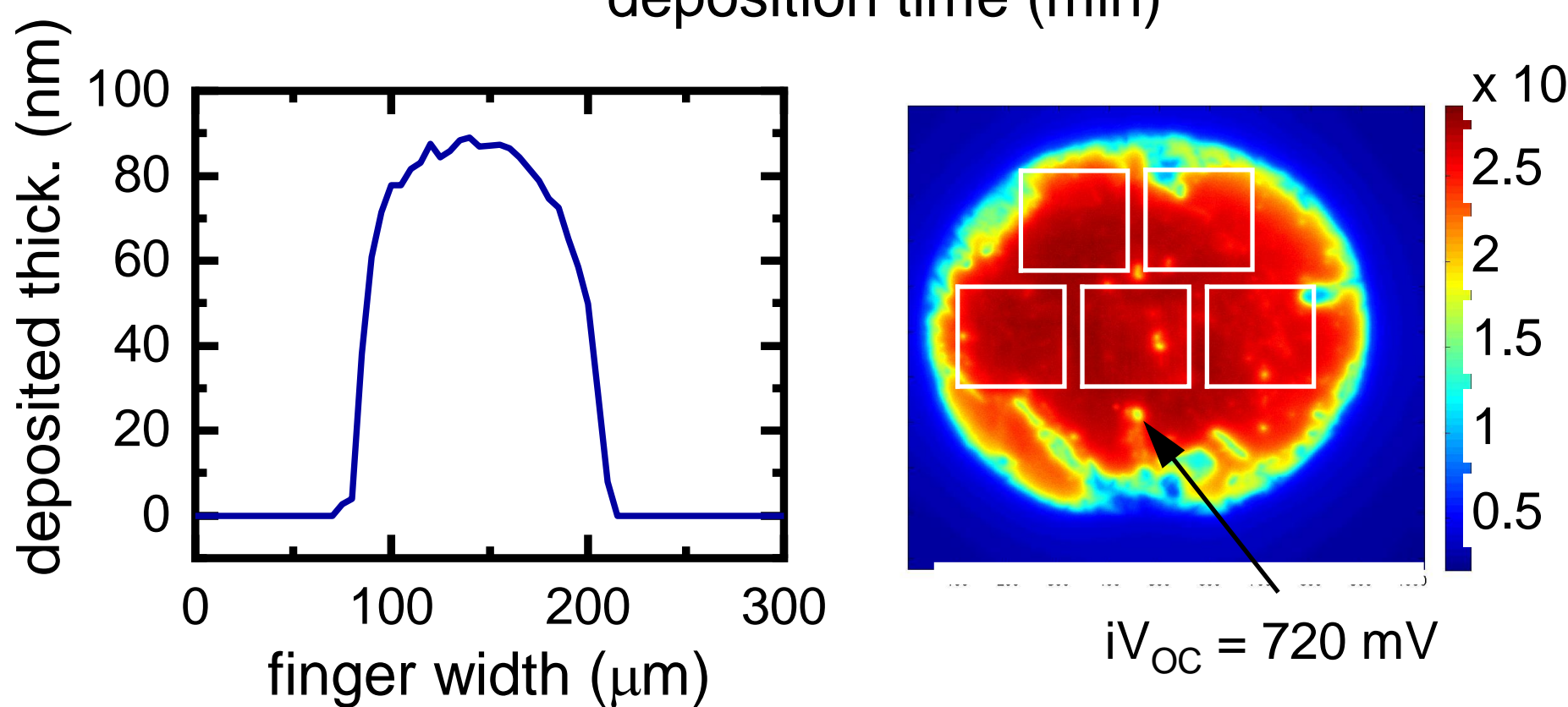
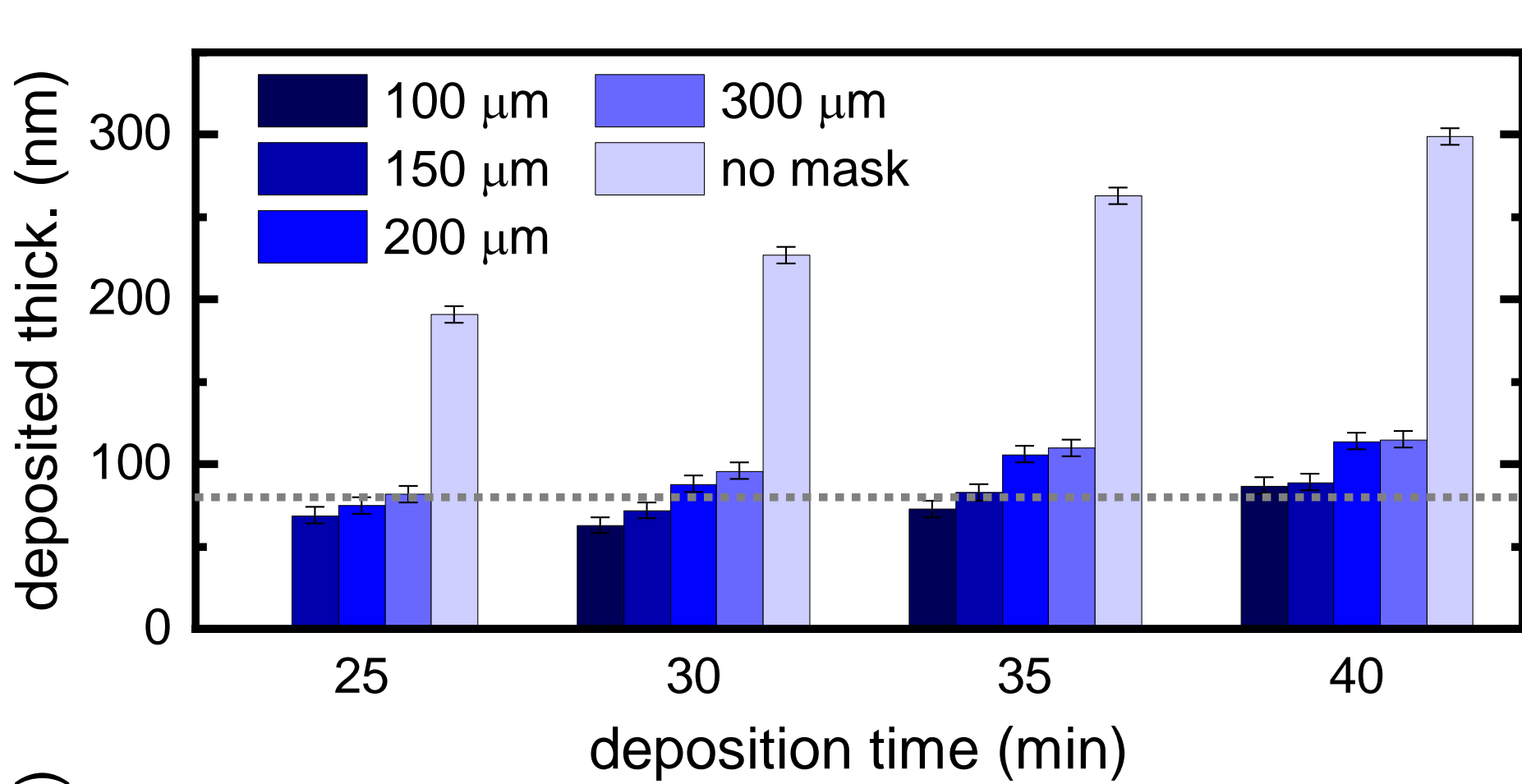
#### Cell demonstrator:

- PECVD deposition of various  $\mu\text{-Si}(n)$  thickness (front) and  $\text{SiC}(p)$  (rear)
- Co-annealing at  $850^\circ\text{C}$
- $\text{SiN}_x$  deposition and Ag paste printing (front)
- Firing (hydrogenation and contacting of the Ag paste)
- metallization with sputtered ITO/Ag stack at the rear



- ✓ Ag paste can be confined in the passivating contacts at 95 nm ( $V_{OC}$  up to 700 mV)
- ✗ Thick passivating contacts are responsible of large parasitic absorptions (low  $J_{SC}$ )

### Localization of Passivating Contacts



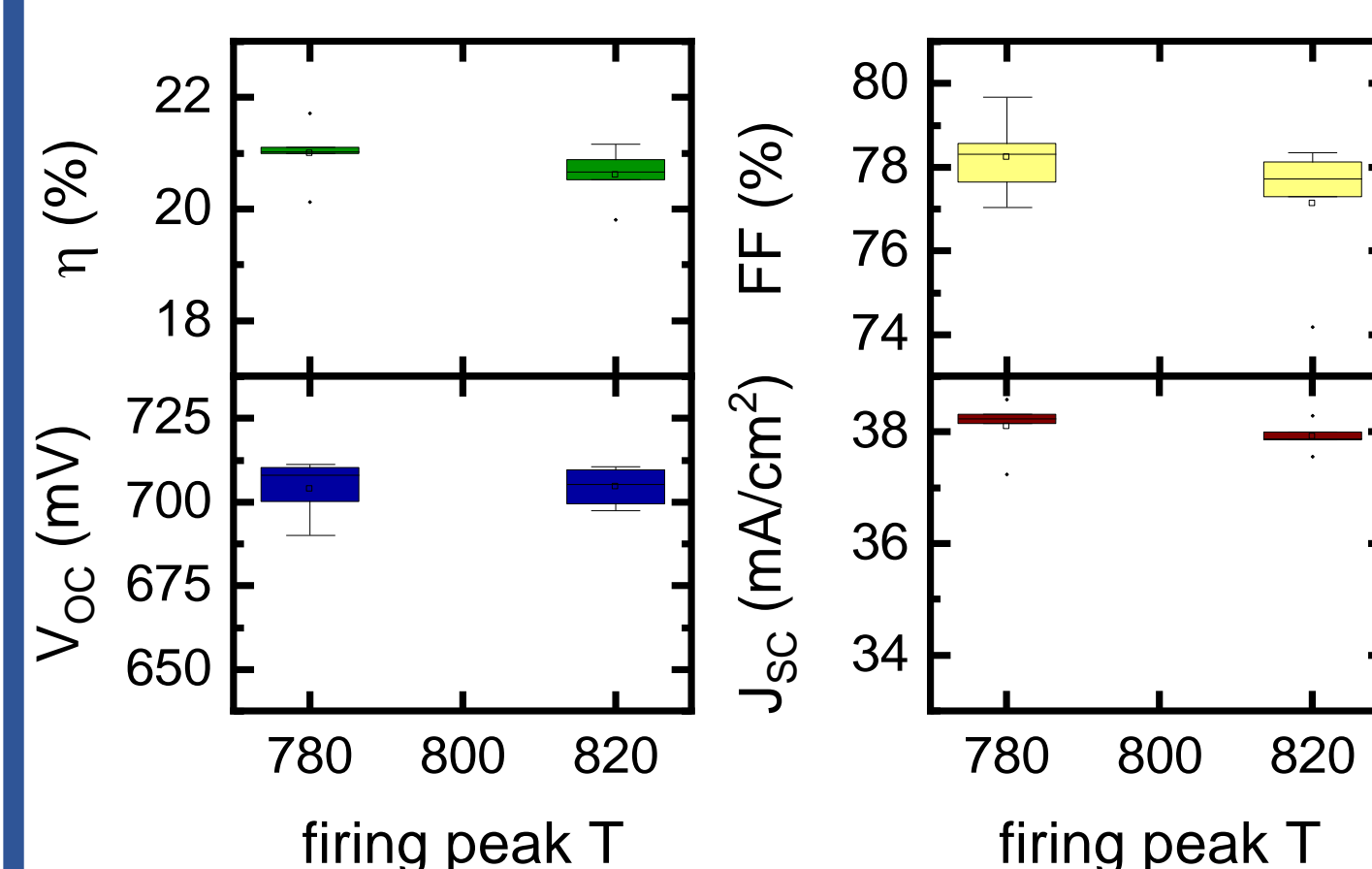
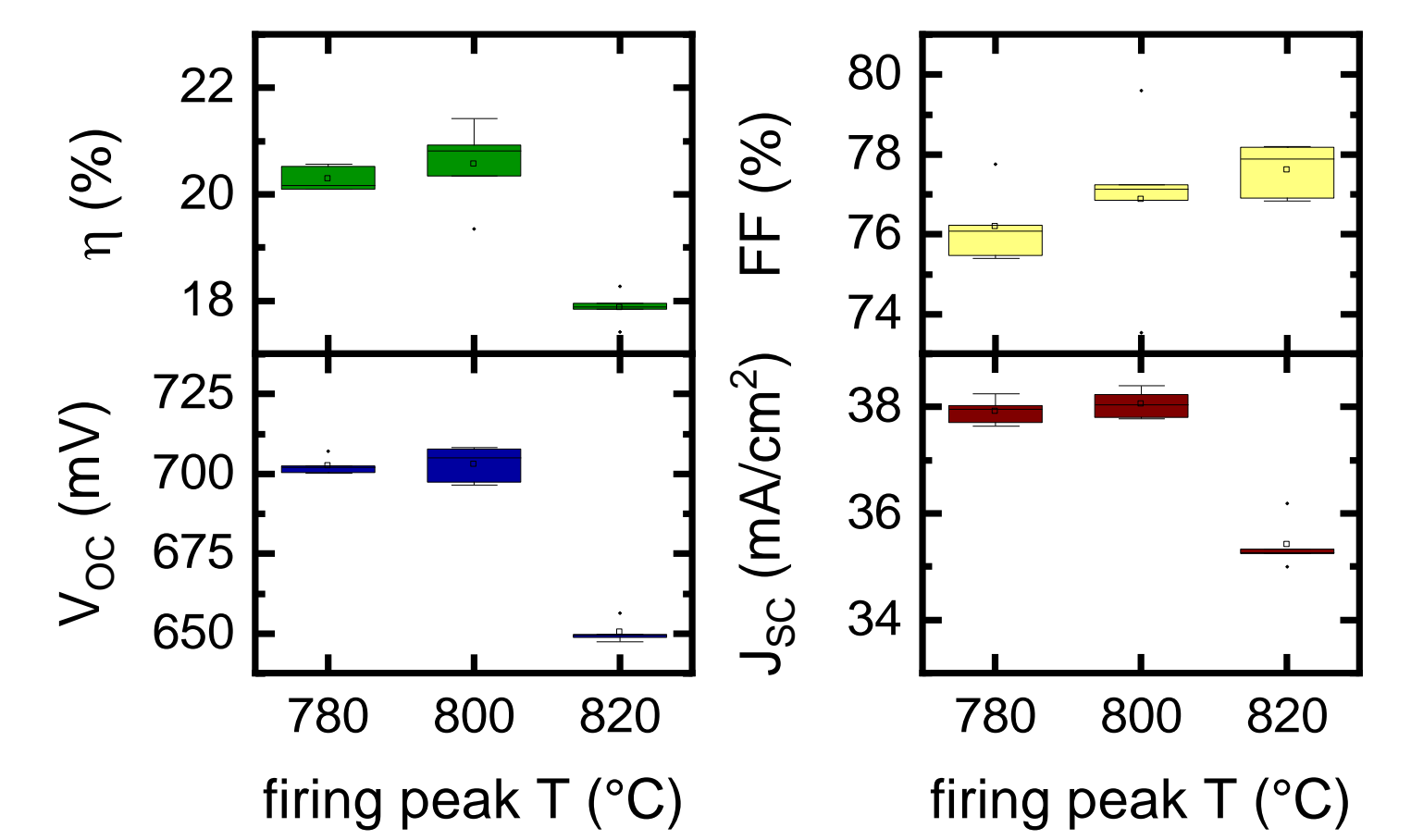
- Localised contacts deposited through hard mask during PECVD
- Localisation can reduce the parasitic absorptions
- Tested on symmetrical structure
- Profile made with Raman spectroscopy<sup>[4]</sup>
- ✓ Feasibility demonstrated up to 100  $\mu\text{m}$
- ✓ Low fingers tapering
- ✓ Homogeneous passivation
- ✗ Large increase of the deposition time

### Solar Cells with Localized Front Passivating Contacts

#### Cell demonstrator:

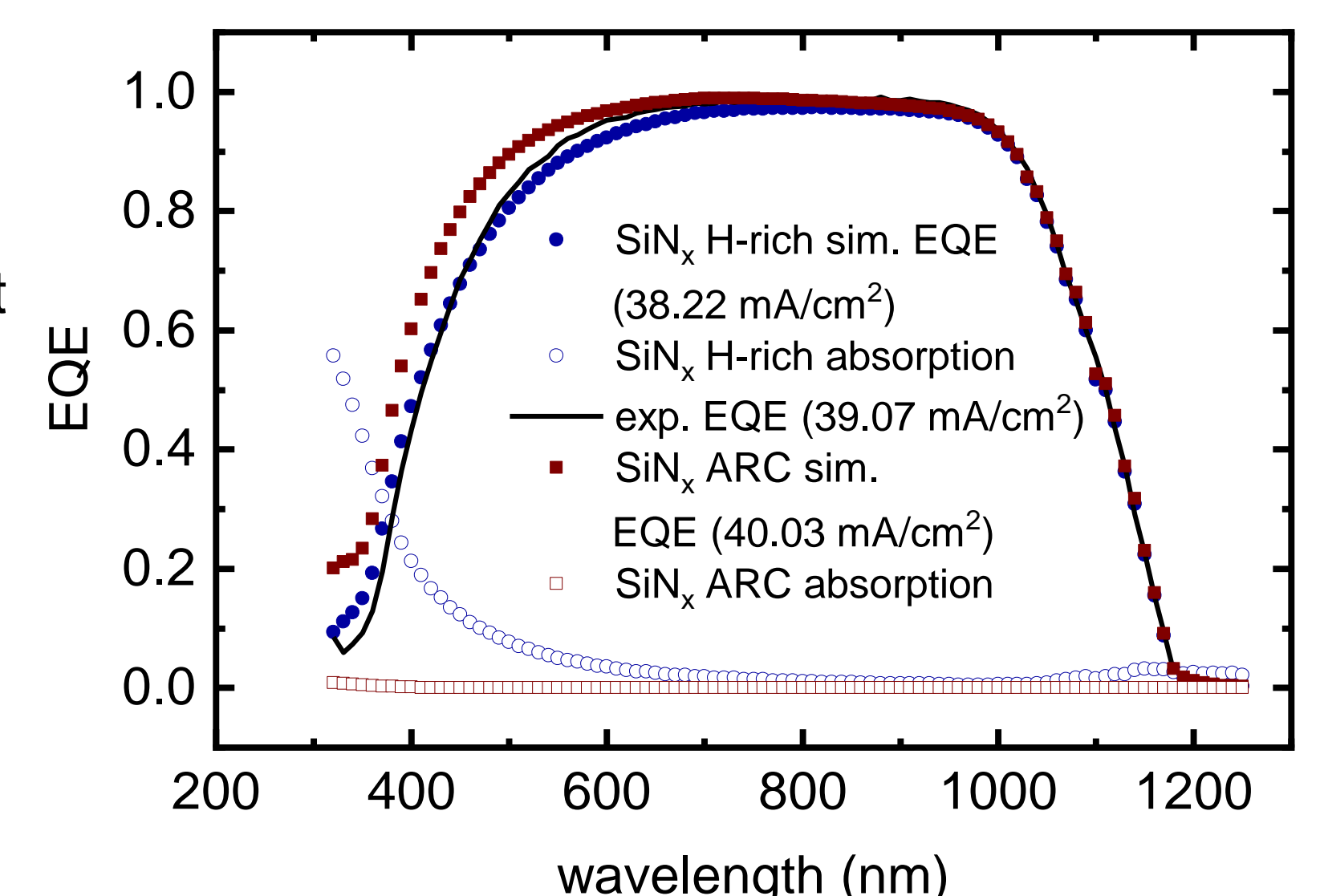
- PECVD deposition of various localized  $\mu\text{-Si}(n)$  thickness, addition of full-area thin  $\mu\text{-Si}(n)$  (front) and  $\text{SiC}(p)$  (rear)
- Co-annealing at  $850^\circ\text{C}$
- $\text{SiN}_x$  deposition and Ag paste printing (front)
- Firing (hydrogenation and contacting of the Ag paste)
- metallization with sputtered ITO/Ag stack at the rear

Thick. (nm)	Eff. (%)	FF (%)	$V_{OC}$ (mV)	$J_{SC}$ (mA/cm <sup>2</sup> )
~100	19.06	79.5	658.6	36.40
~115	21.43	79.6	707.7	38.04
~130	21.72	79.7	711.2	38.32



- ✓ Ag paste can be confined in the passivating contacts even at a firing peak T of  $820^\circ\text{C}$
- ✓  $V_{OC}$  up to 711 mV for the best cell
- ✓ High FF of almost 80 %
- ✗ Final cell efficiency mostly limited by the  $J_{SC}$

- Simulated EQE are compiled with CROWM<sup>[5]</sup> to understand  $\text{SiN}_x$  impact on  $J_{SC}$
- Simulation are in close agreement with reality within a minor error of 2% relative
- $\text{SiN}_x$  optimized for hydrogenation induces large parasitic absorption
- More stoichiometric nitride optimized for ARC could push forward cell eff. over 22.3%



## Conclusion

### Non-Patterned Solar Cells

- Demonstration of thick blistering-free passivating contacts adapted for firing through process
- $V_{OC}$  up to 700 mV
- Thick passivating contacts are responsible of large parasitic absorption  $\rightarrow$  need of patterning for front side application

### Localization of Passivating Contacts

- Demonstration of localization process through hard mask during PECVD
- Low finger tapering and homogenous passivation
- Increase drastically the deposition time  $\rightarrow$  need a better solution to be integrated to industry process

### Solar Cells with Localized Front Passivating Contacts

- Demonstration of high efficiency solar cells  $>21.7\%$  with high  $V_{OC} >710$  mV and high FF  $>79.5\%$
- Final cell efficiency limited by  $J_{SC} \rightarrow$  can be easily improved by using a  $\text{SiN}_x$  optimized for ARC
- Long term objective: contact also the rear during firing through process

## References

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